



## 7<sup>th</sup> IEEE Electron Devices Technology and Manufacturing (EDTM) Conference 2023

March 7 – 10, 2023 / COEX Seoul, Korea

12E. Manufacturing Process Control	
Session Date:	March 8(Wed.), 2023
Session Time:	13:30-15:00
Session Room:	Room E (#308 a)
Session Chair:	Prof. Min Hyuk Park (Seoul National University)
	Prof. Woongkyu Lee (Soongsil University)

[12E-1] [Invited]

13:30-13:55

### Process Control Challenges and Solutions for Advanced Semiconductor Devices

Yun Jung Jee<sup>1</sup>, Sang Hyun Han<sup>2</sup> and Shay Wolfling<sup>3</sup>

<sup>1</sup>Nova Measuring Instruments LTD., <sup>2</sup>Nova Measuring Instruments, Inc. <sup>3</sup>Nova LTD.

[12E-2] [Invited]

13:55-14:20

### Hybrid SPM Metrology and Defect Inspection Technologies in Advanced Process Control

ByungWoon Ahn, Ahjin Jo and Sang-Joon Cho

Park Systems Corp.

[12E-3]

14:20-14:40

### In-line SIMS Enables Better SiGe Epi Process Control for Nanosheets

Lawrence Rooney, Benjamin Hickey, Bruno Schueler, Sarah Okada and Feng Zhang

Nova Inc.

[12E-4]

14:40-15:00

### Budgeting and Predicting Pattern Defects Using Edge Placement Error and Machine Learning

Taekwon Jee<sup>1</sup>, Joonsang You<sup>1</sup>, Hong-Goo Lee<sup>1</sup>, Sang-Ho Lee<sup>1</sup>, Seungmo Hong<sup>1</sup>, Jaewook Seo<sup>1</sup>, Roi Meir<sup>2</sup>, Noam Oved<sup>2</sup>, Jun Park<sup>2</sup>, Shin-Ik Kim<sup>2</sup>, Byung-Jo Lim<sup>2</sup>, Chan-Hee Kwak<sup>2</sup> and Jeong-Ho Yeo<sup>2</sup>

<sup>1</sup>SK hynix, <sup>2</sup>Applied Materials